

Vacuum ▶ PVD Thin films ▶ Leak testing ▶ Plasma



In-line Horizontal Thin Films Sputter system

LINE440



by

allianceconcept

In line deposition equipment.

This equipment offers a **horizontal movement of the substrate** under magnetron sputtering sources. The main advantage of this equipment is to perform the **loading and unloading phases during processing (concurrent time)**. Owing to its multi-level cassette load lock (up to 4 levels) with its vertical movement, the loading operations are realized without disturbing the deposition cycle performed simultaneously.

An activation position by surface etching is used to prepare the surface prior to deposition. Radiant heating can also be installed in the stainless steel vessel, even in the load lock for degassing substrates, or in the deposition chamber to realize coatings in temperature conditions up to 600°C.

Equipped with a PLC, process steps are controlled in automatic mode. LINE440 will be adapted to your very needs. We can also provide on request the vertical built configuration.



Main features

Chamber width :	450 mm
Height :	600 mm
Volume :	120 litres
Ultimate vacuum (turbomolecular configuration) :	5.10^{-7} mbar ^[1]
Ultimate vacuum (cryogenic configuration) :	5.10^{-8} mbar ^[1]
Source configuration :	4
Substrate size :	310 x 400
Thickness uniformity :	< +/- 3% ^[1]
Surface activation and heating :	Yes
Fully automatic system controller :	- Process management - Traceability

^[1] These values have been measured on equipment we have delivered and should be handled as information only. The features of a system depend on its final configuration.

